

<p style="text-align: center;"> O I P E <small>SEARCHED</small> MAY 20 2005 <small>PATENT AND TRADEMARK OFFICE</small> INFORMATION DISCLOSURE STATEMENT BY APPLICANT Form SB/08A <small>(Use several sheets if necessary)</small> </p>			COMPLETE IF KNOWN	
			Application Number	10/721,495
			Confirmation Number	
			Filing Date	November 25, 2003
			First Named Inventor	Michael Kenny
			Group Art Unit	
			Examiner Name	
1	of	1	Attorney Docket No.	54008.8100.US01 (P01-0015US2)

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent or Application		Name of Patentee or Applicant of Cited Document	Date of Publication or Filing Date of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T
		Office	NUMBER				
							X
							X
							X

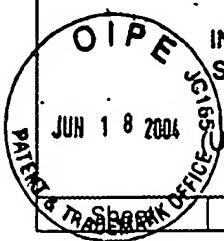
OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume issue number(s), publisher, city and/or country where published.	T

EXAMINER 	DATE CONSIDERED 9/30/06
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*EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not

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INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
Form PTO-1449 (Modified)
Use several sheets if necessary)

COMPLETE IF KNOWN

Application Number	10/721,495
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First Named Inventor	Michael KENNY
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1 of 4

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		NUMBER	Kind Code (if known)			
JWS	DO	6,551,409		DeGendt	04/22/03	
JWS	DP	2002/0011257		DeGendt	01/31/02	

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JWS	DQ	Alder, M., et al., "The Kinetics and Mechanism of Hydroxide Ion Catalyzed Ozone Decomposition in Aqueous Solution." <i>J. Am. Chem. Soc.</i> , 72:1884-1886 (1950).	
	DR	Amick, J.A., "Cleanliness and the Cleaning of Silicon Wafers." <i>Solid State Technology</i> , pp. 47-52 (Nov. 1976).	
	DS	Anantharaman, et al., "ORGANICS: Detection and Characterization of Organics in Semiconductor DI Water Processes." <i>Ultrapure Water</i> , pp. 30-36 (Apr. 1994).	
	DT	Baumgärtner, H., et al., "Ozone Cleaning of the Si-SiO ₂ System." <i>Appl. Phys. A</i> , 43:223-226 (1987).	
	DU	Bedge, S., et al., "Kinetics of UV/O ₂ Cleaning and Surface Passivation: Experiments and Modeling." <i>Mat. Res. Soc. Symp. Proc.</i> , 259:207-212 (1992).	
	DV	Bolon, D.A., et al., "Ultraviolet Depolymerization of Photoresist Polymers," <i>Polymer Engineering and Science</i> , 12(2):108-111 (March 1972)	
JWS	DW	Christenson, K., et al., "Deionized Water Helps Remove Wafer Stripping 'Resist'-ance." www.precisioncleaningweb.com--Precision Cleaning Web-Archives , pp. 10-20 (Apr. 1998).	

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<i>JWS</i>	4/30/04

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MWS	DX	Egitto, F.D., et al., "Removal of Poly (Dimethylsiloxane) Contamination From Silicon Surfaces With UV/Ozone Treatment." <i>Mat. Res. Soc. Symp. Proc.</i> , 385:245-250 (1995).			
	DY	Gabriel, C., et al., "Reduced Device Damage Using An Ozone Based Photoresist Removal Process." <i>SPIE Advances in Resist Technology and Processing VI</i> , 1086:598-604 (1989).			
	DZ	Ganesan, G., et al., "Characterizing Organic Contamination in IC Package Assembly." <i>The Int'l. Soc. for Hybrid Microelectronics</i> , 17(2), Second Quarter, 152-160 (1994).			
	EA	Golland, D.E., et al., "The Clean Module: Advanced Technology for Processing Silicon Wafers." <i>Semiconductor Int'l.</i> , pp. 154-157 (Sep. 1987).			
	EB	Goulding, M.R., "The selective epitaxial growth of silicon," <i>Materials Science and Engineering</i> , Vol. B17, pp. 47-67 (1993).			
	EC	Heyns, M.M., et al., "New Wet Cleaning Strategies for Obtaining Highly Reliable Thin Oxides." <i>MRP Symposium Proceedings on Materials Research Society</i> , Spring Meeting, San Francisco, CA, Apr. 12-13, p. 35 (1993).			
	ED	Huynh, C., et al., "Plasma versus ozone photoresist ashing: Temperature effects on process-induced mobile ion contamination." <i>J. Vac. Sci. Technol.</i> , B9(2):353-356 (Mar./Apr. 1991).			
	EE	Isagawa, T., et al., "Ultra Clean Surface Preparation Using Ozonized Ultrapure Water." <i>Extended Abstracts of the 1992 Int'l. Conf. on Solid State Devices and Materials</i> , pp. 193-195 (1992).			
	EF	Kasi, S., et al., "Surface Hydrocarbon Removal from Si by UV/Ozone." <i>ECS Extended Abstracts</i> , No. 458, pp. 691-692 (1990).			
	EG	Kasi, S., et al., "Vapor phase hydrocarbon removal for Si processing." <i>Appl. Phys. Lett.</i> , 57(20):2095-2097 (Nov. 1990).			
MWS	EH	Kern, W., "The Evolution of Silicon Wafer Cleaning Technology." <i>J. Electrochem. Soc.</i> , 137(6):1887-1892 (Jun. 1990).			

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[54008.8100.US01/LA041610.019]	

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Sheet	3	of	4	Application Number	10/721,495
				Confirmation Number	
				Filing Date	November 25, 2003
				First Named Inventor	Michael KENNY
				Group Art Unit	
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				Attorney Docket No.	54008.8100.US01 (P01-0015US2)

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JWS	EI	Krusell, W.C., et al., "Cleaning Technologies for High Volume Production of Silicon Wafers." <i>ECS Proc. of the First Int'l. Symposium on Cleaning Technology in Semiconductor Device Mfg.</i> , pp. 23-32 (Oct. 1989).			T
	EJ	Krusell, W.C., et al., "The Characterization of Silicon Substrate Cleaning Treatments by use of SIMS and MOS Electrical Testing." <i>ECS Extended Abstracts</i> , No. 229, p. 331-332 (1986).			
	EK	Nelson, S., "Ozonated water for photoresist removal." <i>Solid State Technology</i> , p. 107-112 (Jul. 1999).			
	EL	Ohmi, T., et al., "Native Oxide Growth and Organic Impurity Removal on Si Surface with Ozone-Injected Ultrapure Water." <i>J. Electrochem. Soc.</i> , 140(3):804-810 (Mar. 1993).			
	EM	Sehested, K., et al., "Decomposition of Ozone in Aqueous Acetic Acid Solutions (pH 0-4)." <i>J. Phys. Chem.</i> , pp. 1005-1009 (1992).			
	EN	Shimada, H., et al., "Residual-Surfactant-Free Photoresist Development Process." <i>J. Electrochem. Soc.</i> , 139(6):1721-1730 (Jun. 1992).			
	EO	Suemitsu, M., et al., "Low Temperature Silicon Surface Cleaning by HF Etching/Ultraviolet Ozone Cleaning (HF/UVOC) Method (I)-Optimization of the HF Treatment." <i>Japanese Journal of Applied Physics</i> , 28(12):2421-2424 (Dec. 1989).			
	EP	Tabe, M., "UV ozone cleaning of silicon substrates in silicon molecular beam epitaxy." <i>Appl. Phys. Lett.</i> , 45(10):1073-1075 (Nov. 1984).			
	EQ	Tong, J., et al., "Aqueous Ozone Cleaning of Silicon Wafers." <i>ECS Extended Abstracts</i> , Phoenix, AZ, Abstract No. 506, pp. 753 (Oct. 13-17, 1991).			
	ER	Tong, J., et al., "Aqueous Ozone Cleaning of Silicon Wafers." <i>Proc. of 2.sup.nd Int'l. Symposium on Cleaning Tech. In Semiconductor Device Mfg.</i> , pp. 18-25 (Oct. 1992).			
	ES	Vig, J., "UV/Ozone Cleaning of Surfaces." <i>U.S. Army Elec. Tech. and Devices Lab.</i> , pp. 1-26.			
JWS	ET	Vig, J., "UV/Ozone Cleaning of Surfaces: A Review." <i>Surface Contamination: Genesis, Detection, and Control</i> , pp. 235-253 (1979).			

EXAMINER	DATE CONSIDERED
	7/31/06
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[54008.8100.US01/LA041610.019]

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				Confirmation Number	
				Filing Date	November 25, 2003
				First Named Inventor	Michael KENNY
				Group Art Unit	
				Examiner Name	
Sheet	4	of	4	Attorney Docket No.	54008.8100.US01 (P01-0015US2)

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<i>MNS</i>	EU	Vig, J., et al., "UV/Ozone Cleaning of Surfaces." <i>IEEE Transactions on Parts, Hybrids, and Packaging</i> , Vol. PHP-12(4):365-370 (Dec. 1976).				
	EV	Vig, J., "UV/Ozone Cleaning of Surfaces." <i>U.S. Army Electronics Technology and Devices Laboratory</i> , ERADCOM, Ft. Monmouth, NJ, 07703-5302, pp. 1027-1034 (Sep./Oct. 1984).				
	EW	Zafonte, L., et al., "UV/Ozone Cleaning For Organics Removal on Silicon Wafers." <i>SPIE Optical Microlithography III: Technology for the Next Decade</i> , 470:164-175 (1984).				
	EX	Zazzera, L.A., et al., "XPS and SIMS Study of Anhydrous HF and UV/Ozone-Modified Silicon (100) Surfaces." <i>J. Electrochem. Soc.</i> , 136(2):484-491 (Feb. 1989).				
	EY	"Ozone Concentration Measurement in a Process Gas." <i>Proposed IOA Pan American Group Guideline</i> , pp. 1-21 (Dec. 1993).				
<i>MNS</i>	EZ	"Ozone for Semiconductor Applications." <i>Sorbios</i> , pp. 1-6 (Oct. 1991).				

EXAMINER	DATE CONSIDERED
<i>M. Stone</i>	4/30/06
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT Form SB/08A (Use several sheets if necessary)				COMPLETE IF KNOWN	
				Application Number	10/721,485
				Confirmation Number	6048
				Filing Date	November 25, 2003
				First Named Inventor	Michael Kenny
				Group Art Unit	1746
				Examiner Name	Frankie L. Stinson
				Attorney Docket No.	54008.8100.US01 (P05-0015US2)
Sheet	1	of	4		



U.S. PATENT DOCUMENTS					
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		Number-Kind Code ² (if known)			
JWS	FB	4,064,885	12-1977	Dussault et al.	
	FC	4,633,804	01-1987	Arii	
	FD	4,695,327	09-1987	Grebinski	
	FE	4,778,532	10-1988	McConnell et al.	
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	FI	5,423,944	03-1994	Wong	
	FJ	5,518,542	05-1996	Matsukawa et al.	
	FK	5,868,866	02-1999	Maekawa et al.	
	FL	5,911,836	06-1999	Hada et al.	
	FM	5,922,624	07-1999	Verhaverbeke et al.	
	FN	5,927,306	Jul-99	Izumi et al.	
	FO	5,975,098	11-1999	Yoahitani et al.	
	FP	5,990,060	11-1999	Ohmi et al.	
	FQ	6,003,527	12-1999	Netsu et al.	
	FR	6,085,764	07-2000	Kobayashi	
	FS	6,199,567	03-2001	Kanno et al.	
	FT	6,202,658	03-2001	Fishkin et al.	
	FU	6,235,112	05-2001	Satoh	
	FV	6,240,933	06-2001	Bergman	
	FW	6,295,999	10-2001	Bran	
	FX	6,325,081	12-2001	Miki et al.	
	FY	6,406,551	06-2002	Nelson et al.	
	FZ	6,423,146	07-2002	Fukazawa	
JWS	GA	6,431,184	08-2002	Taniyama	

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Sheet	2	of	4	Application Number	10/721,495
				Confirmation Number	6048
				Filing Date	November 25, 2003
				First Named Inventor	Michael Kenny
				Group Art Unit	1746
				Examiner Name	Frankie L. Stinson
				Attorney Docket No.	S4008.8100.US01 (P05-0015US2)

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		Number-Kind Code ² (if known)			
JWS	GB	6,455,717	09-2002	Vaartstra	
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	GH	6,817,370	11-2004	Bergman et al.	
	GI	6,843,857	01-2005	Bergman	
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		Country Code	Number-Kind Code (if known)				
JWS	GM	DE	19801360 A1	7/22/1999	SEZ Semiconductor-Equipment Zubehor		
	GN	EP	0 587 889	03-23-1994	Ohmi, Tadahiro		
	GO	EP	0 890 658	01-1999			
	GP	GB	2 287 827	09-27-1995	NEC Corporation		
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	GX	JP	09-139345	05-1997			
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	HB	JP	61-004232	01-10-1986	NEC Corp.		
	HC	JP	2000-138188	05-2000			
AJNS	HD	WO	WO01/07177 A1	02-01-2001	Semitool, Inc.		

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(JWS)	HE	Bergman, E. et al., "HF-Ozone Cleaning Chemistry," Solid State Technology 46(7):115-124(2001)		

JWStinson 4/26/06